

	<b>Hits</b>	<b>Search Text</b>	<b>DBs</b>
<b>1</b>	69	((resist or photoresist) same pattern) and ((resist or photoresist) same (smooth\$4 or cover\$4 or thicken\$5 or enhanc\$4) same (coat\$4 or layer or film)) and etch\$4 and ((resist or photoresist) same pattern same (dimension or measurement or characteristic)) and (uniformity same (pattern or hole or via)) and (striation or unevenness)	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB
<b>2</b>	84	((resist or photoresist) same pattern) and ((resist or photoresist) same (smooth\$4 or cover\$4 or thicken\$5 or enhanc\$4) same (coat\$4 or layer or film)) and etch\$4 and ((resist or photoresist) same (dimension or measurement or characteristic)) and ((striation or roughness or variation or var\$4) same (resist or photoresist) same (pattern or via or hole) same uneven\$5)	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB
<b>3</b>	36	((resist or photoresist) same pattern) and ((resist or photoresist) same (smooth\$4 or cover\$4 or thicken\$5 or enhanc\$4) same (coat\$4 or layer or film)) and etch\$4 and ((resist or photoresist) same (dimension or measurement or characteristic)) and ((striation or roughness or variation or var\$4) same (resist or photoresist) same (pattern or via or hole) same uneven\$5) and uniformity	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB